

AMENDMENTS TO THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

LISTING OF CLAIMS:

Claims 1-18 (canceled).

Claim 19 (new): A method for forming a thick film pattern, comprising the steps of:

applying to a support a photosensitive paste including an inorganic powder, a photosensitive monomer, and a photopolymerization initiator and containing substantially no polymer so as to form a photosensitive paste film;

subjecting the photosensitive paste film to an exposure treatment; and

developing the photosensitive paste film subjected to the exposure treatment so as to form a thick film pattern.

Claim 20 (new): A method for forming a thick film pattern, comprising the steps of:

applying to a support a photosensitive paste including an inorganic powder, a photosensitive monomer, a photopolymerization initiator, and a polymer, wherein a ratio of the photosensitive monomer to a total amount of the photosensitive monomer and the polymer satisfies the condition represented by the following Formula:

photosensitive monomer/(photosensitive monomer + polymer) \geq 0.86,

so as to form a photosensitive paste film;

subjecting the photosensitive paste film to an exposure treatment; and

developing the photosensitive paste film subjected to the exposure treatment so as to form a thick film pattern.

Claim 21 (new): The method for forming a thick film pattern according to Claim 19, wherein the contents of the inorganic powder, the photosensitive monomer, and the photopolymerization initiator constituting the photosensitive paste are within the following ranges:

inorganic powder: about 60 to about 90 percent by weight;

photosensitive monomer: about 5 to about 39 percent by weight; and

photopolymerization initiator: about 1 to about 10 percent by weight.

Claim 22 (new): The method for forming a thick film pattern according to Claim 19, wherein the photosensitive paste includes a photosensitive monomer having a double bond concentration within the range of about 8 mmol/g to about 11 mmol/g.

Claim 23 (new) The method for forming a thick film pattern according to Claim 19, wherein the photosensitive paste includes a photosensitive monomer having an ethylene oxide structure with a degree of polymerization of about 3 or less.

Claim 24 (new): The method for forming a thick film pattern according to Claim 19, wherein the photosensitive paste comprises an ultraviolet absorber.

Claim 25 (new): The method for forming a thick film pattern according to Claim 19, wherein the photosensitive paste comprises a solvent in a proportion of about 5 percent by weight or less.

Claim 26 (new): The method for forming a thick film pattern according to Claim 19, wherein development is conducted by using an organic solvent in the development step.

Claim 27 (new): The method for forming a thick film pattern according to Claim 19, wherein the exposure treatment is conducted while the photosensitive paste film and a photomask are arranged to be kept from contacting with each other in the exposure step.

Claim 28 (new): The method for forming a thick film pattern according to Claim 19, wherein the photosensitive paste is subjected to the exposure treatment without using a photomask in the exposure step.

Claim 29 (new): A method for manufacturing an electronic component, comprising the steps of:

forming a thick film pattern by the method according to Claim 19; and
firing the resulting thick film pattern.

Claim 30 (new): A photolithography photosensitive paste comprising an inorganic powder, a photosensitive monomer, and a photopolymerization initiator and comprising substantially no polymer.

Claim 31 (new): A photolithography photosensitive paste comprising:
an inorganic powder;
a photosensitive monomer;
a photopolymerization initiator; and
a polymer; wherein
a ratio of the photosensitive monomer to a total amount of the photosensitive monomer and the polymer satisfies the condition represented by the following Formula:
$$\text{photosensitive monomer} / (\text{photosensitive monomer} + \text{polymer}) \geq 0.86.$$

Claim 32 (new): The photolithography photosensitive paste according to Claim 30, wherein the contents of the inorganic powder, the photosensitive monomer, and the photopolymerization initiator are within the following ranges:

inorganic powder: about 60 to about 90 percent by weight,
photosensitive monomer: about 5 to about 39 percent by weight, and
photopolymerization initiator: about 1 to about 10 percent by weight.

Claim 33 (new): The photolithography photosensitive paste according to Claim 30, wherein the photosensitive monomer is a photosensitive monomer having a double bond concentration within the range of about 8 mmol/g to about 11 mmol/g.

Claim 34 (new): The photolithography photosensitive paste according to Claim 30, wherein the photosensitive monomer is a photosensitive monomer having an ethylene oxide structure with a degree of polymerization of about 3 or less.

Claim 35 (new): The photolithography photosensitive paste according to Claim 30, further comprising an ultraviolet absorber.

Claim 36 (new): The photolithography photosensitive paste according to Claim 30, further comprising a solvent in a proportion of about 5 percent by weight or less.